News Release

July 23, 2025
JX Advanced Metals Corporation

Strengthening the Supply System for High-Purity CVD and ALD Materials Essential for the High Performance of Next-Generation Semiconductors
- Supporting the Continued Advancement of Rapidly Growing Generative AI -

JX Advanced Metals Corporation (President: Yoichi Hayashi, hereinafter "the Company") has been strengthening its supply system in response to the rapid rise in demand for CVD and ALD materials(1 for next-generation semiconductors. We are pleased to announce that the expansion of production facilities within Toho Titanium's Chigasaki Plant Premises, which was being promoted through investment by our company, has been completed and full operation has started. In addition, we are introducing production facilities at our Ibaraki Office (Hitachi Area) to meet future market expansion.

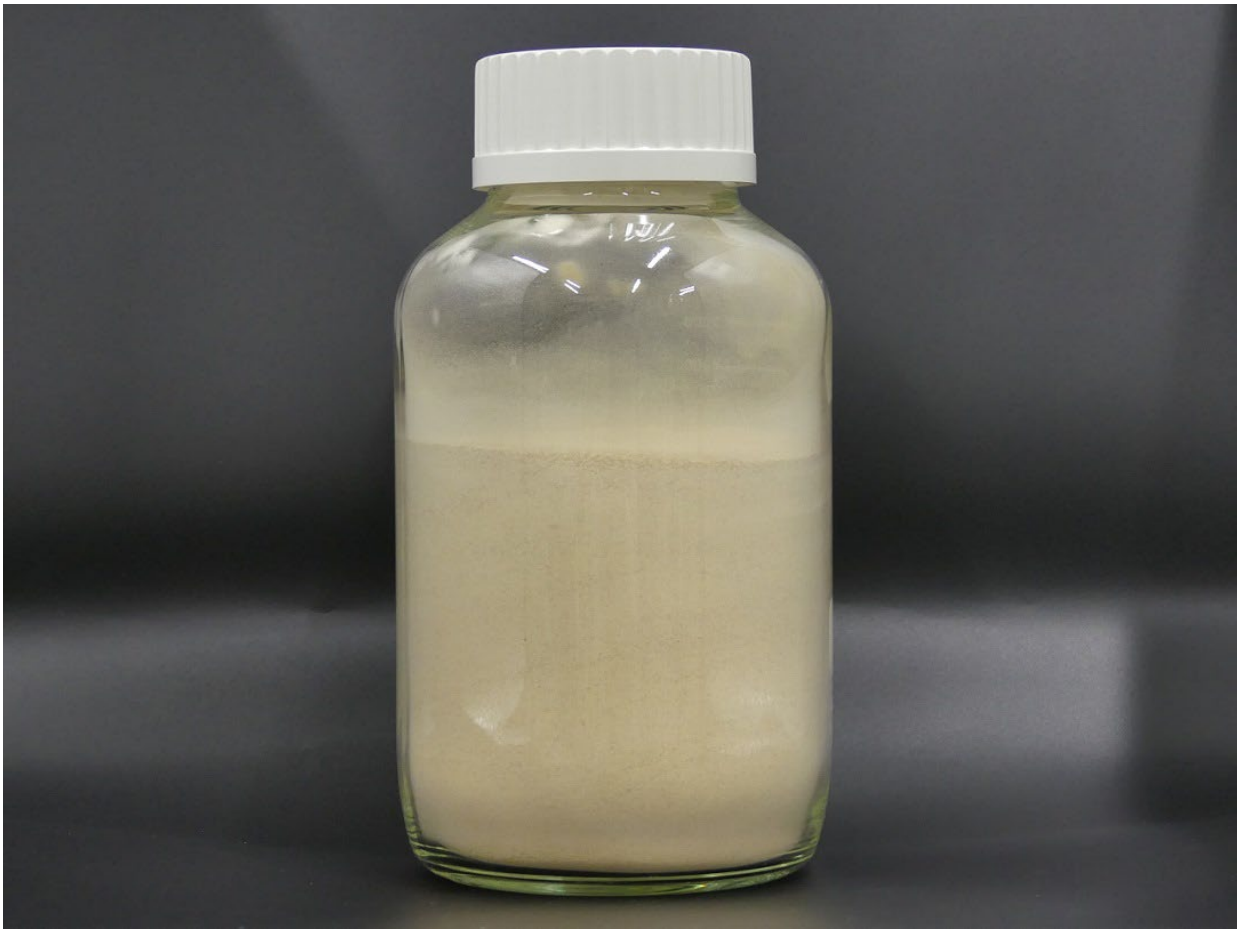
Semiconductor devices such as logic chips and 3D-NAND flash memories and HBMs, which underpin the evolution of generative AI, are achieving higher performance through finer design rules and more complex wiring structures. This has led to growing demand for CVD and ALD materials, which play an essential role in forming such fine and complex wiring structures. On the other hand, with the progress of next-generation semiconductor scaling, challenges such as increased wiring resistance and noise have emerged, and there is a growing trend to adopt new materials as well as to change the wiring architecture as a solution. Among the CVD and ALD materials recently launched by the Company, our molybdenum compounds offer a promising solution. Molybdenum compounds, one of the CVD/ALD materials that we have recently started manufacturing, not only provide a solution to these challenges, but can also be expected to contribute to yield improvement since impurities are reduced by our proprietary high-purity technology.

In addition to our domestic facilities, in November 2024, our group company TANIOBIS GmbH, based in Germany, began operating new equipment capable of developing and producing a wide variety of CVD and ALD materials(2, strengthening our global supply system and ensuring a stable supply and business continuity. Going forward, we will continue to leverage the extensive expertise and networks we have cultivated through our sputtering target business and other semiconductor-related operations, expanding our CVD and ALD materials business across the entire group.

Under the "Long-Term Vision for 2040", we are committed to transforming into a technology-driven company and contributing to societal progress and innovation through advanced materials as a global leader.

【Reference】
Note (1; For more information on strengthening of supply system, please refer to the press release, July 18, 2024 " Decision to Increase Capacity for Full-Scale Production of CVD and ALD Materials for Next-Generation Semiconductors "
Note (2; For more information on strengthening of supply system at TANIOBIS GmbH, November 13, 2024 " Operations Launched at TANIOBIS in Germany for the Development and Production of High-Purity Metal Compounds -Powering an Expansion in Our Portfolio of CVD and ALD Precursor Materials for Semiconductors- "

Corporate Communication Department, JX Advanced Metals Corporation
The Okura Prestige Tower 10-4, Toranomon 2-chome, Minato-ku, Tokyo 105-8417, Japan TEL: +81-3-6433-6056



Picture of Molybdenum Compounds

Corporate Communication Department, JX Advanced Metals Corporation
The Okura Prestige Tower 10-4, Toranomon 2-chome, Minato-ku, Tokyo 105-8417, Japan TEL: +81-3-6433-6056